A Comprehensive Investigation of Raman Laser-Induced Structural Modification in CVD-Grown Monolayer MoS₂

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Figure S1. Effect of laser irradiation on monolayer MoS_2 . (a) Raman intensity mapping image at A' vibration mode. (b) Raman intensity mapping image at the hydrogenated amorphous carbon (a:C-H) peak. The scale bars represent 1 μ m. (c) AFM topography image of (a) and (b) with part of the laser spot scratched. (d) Schematic illustration depicting the effects on monolayer MoS_2 relative to the spatial distribution of the laser intensity and its interaction with the sample.



Figure S2. Raman spectra of E' and A' vibration modes in the range of $375 \sim 420 \text{ cm}^{-1}$ according to the power and exposure time. The spectra are normalized to the A' vibration mode. The A' vibration mode exhibits a slight blue-shift ($\sim 407 \text{ cm}^{-1}$) at a laser power of 40 mW.

Table S1. Calculated maximum temperature of the top surface of the Si substrate according to the laser power.

		10.37 mW	20.14 mW	40.48 mW	51.82 mW
D	(µm)	0.74	0.74	0.74	0.74
q"laser, average	(W/cm^2)	2.41×10^{6}	4.68×10^{6}	9.41x10 ⁶	1.29x10 ⁷
T _{Si, top, max}	(K)	373.19	443.89	591.08	673.15
	(°C)	100.04	170.74	317.93	400.00